The Development and the commercialization of the Mask Aligner for wafer

Midas System will continue to grow along with the value creation for our customers.

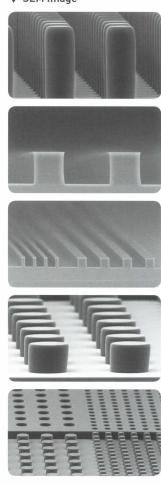
MDA-400LJ



The MDA-400LJ is used for Semiconductor & Application Process. This machine can make a higher Performance of Process. It is ideal, economical unit for University and Research center.



▼ SEM Image



ITEM	SPECIFICATION
Substrate Size	Up to 4 inch
Light source	UV LED
Resolution	1μm with 1μm thin PR @ Si wafer
Alignment Accuracy	$\pm 1 \mu \mathrm{m}$
I-line Beam Intensity	About 10mW/cm²
Process Mode	Soft, Hard, Vacuum and Proximity

